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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
09/976,641	10/12/2001	Daniel Xu	INTO-0004-US	2057	
7:	590 01/30/2004		EXAMINER		
Timothy N. Trop			BAUMEISTER, BRADLEY W		
	TROP, PRUNNER & HU, P.C. 8554 KATY FWY		ART UNIT	PAPER NUMBER	
SUITE 100 HOUSTON, TX 77024-1805			2815		
			DATE MAILED: 01/30/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)					
Advisory Action	09/976,641	XU ET AL.					
Advicery Neticin	Examiner	Art Unit					
	B. William Baumeister	2815	NU)				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address							
THE REPLY FILED 02 January 2004 FAILS TO PLACE Therefore, further action by the applicant is required to a final rejection under 37 CFR 1.113 may only be either: (1 condition for allowance; (2) a timely filed Notice of Appearance (1) and (1) compliance with 37 CFR 1.114.	void abandonment of this applice I) a timely filed amendment whi	cation. A proper rep ch places the applic	oly to a cation in				
PERIOD FOR RE	PLY [check either a) or b)]						
a) The period for reply expires 3 months from the mailing date of	-						
b) L. The period for reply expires on: (1) the mailing date of this Adv event, however, will the statutory period for reply expire later the ONLY CHECK THIS BOX WHEN THE FIRST REPLY WAS 706.07(f).  Extensions of time may be obtained under 37 CFR 1.136(a). The dath have been filled is the date for purposes of determining the period of extens 37 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened (b) above, if checked. Any reply received by the Office later than three moderned patent term adjustment. See 37 CFR 1.704(b).	an SIX MONTHS from the mailing date o FILED WITHIN TWO MONTHS OF THI te on which the petition under 37 CFR 1.1 sion and the corresponding amount of the I statutory period for reply originally set in	f the final rejection. E FINAL REJECTION. S I 36(a) and the appropriate e fee. The appropriate ext the final Office action; or	See MPEP e extension fee ension fee under (2) as set forth in				
1. A Notice of Appeal was filed on Appellant's 37 CFR 1.192(a), or any extension thereof (37 CF	R 1.191(d)), to avoid dismissal						
2. The proposed amendment(s) will not be entered be							
(a) they raise new issues that would require furth		(see NOTE below);					
(b) they raise the issue of new matter (see Note because of the second o	•						
<ul><li>(c) they are not deemed to place the application issues for appeal; and/or</li></ul>	in better form for appeal by mat	erially reducing or s	simplifying the				
(d) they present additional claims without cancel NOTE:	ling a corresponding number of	finally rejected clair	ns.				
3. Applicant's reply has overcome the following rejection.	ction(s): the amendment overco	mes the 112-2 <sup>nd</sup> par	ragrpah				
4. Newly proposed or amended claim(s) would canceling the non-allowable claim(s).	be allowable if submitted in a s	separate, timely filed	d amendment				
5. ☐ The a) ☐ affidavit, b) ☐ exhibit, or c) ☒ request for reconsideration has been considered but does NOT place the application in condition for allowance because: <u>See Continuation Sheet</u> .							
6. The affidavit or exhibit will NOT be considered be raised by the Examiner in the final rejection.	cause it is not directed SOLELY	to issues which we	re newly				
7. For purposes of Appeal, the proposed amendment explanation of how the new or amended claims w			and an				
The status of the claim(s) is (or will be) as follows:							
Claim(s) allowed:							
Claim(s) objected to:							
Claim(s) rejected: <u>11-14 and 16-30</u> .			٨				
Claim(s) withdrawn from consideration:			/\				
] The drawing correction filed on is a) ☐ approved or b) ☐ disapproved by the Examiner. ▮ / │							
9.  Note the attached Information Disclosure Statement(s)( PTO-1449) Paper No(s)							
10. Other:							
1	B.WILLIAM BAUMEISTER PRIMARY EXAMINER	B. William Baumei Primary Examiner Art Unit: 2815	ister				

Continuation of 5. does NOT place the application in condition for allowance because:

Applicant argues that (1) while Ovshinsky teaches the inclusion of a more lightly-doped n-type region over the heavily-doped region, this lightly-doped region in Ovshinsky is formed so as to be in an epitaxial layer as opposed to being in the bulk substrate, and (2) that Chang--which does teach the formation of diodes in only bulk substrates as opposed to also in epitaxial layers--does not teach the inclusion of a more lightly-doped superposed layer, and as such, the combination of these references does not render the claims obvious. This argument is not persuasive because Chang was not relied upon for the teaching of including a more lightly-doped superposed layer. Rather, as Applicant akcnowledged, this region was taught by Ovshinsky. Chang was relied upon for evidencing the propositions that (1) it was known to form a more lightly-doped region under the heavily-doped region within the substrate and (2) forming all three of these regions as taught by either Ovshinsky or Chang so as to be only in a bulk substrate was a functional equivalent to forming them in the bulk substrate and in the epitaxial region.

Applicant further argues that the fact, that neither Ovshinsky nor Chang specifically teaches the upper lightly-doped region may be formed in the bulk instead of the epitaxial region, indicates that neither Chang nor Ovshinsky had any idea how to make a more lightly doped region/heavily doped region/lightly doped region in the substrate. This argument is not persuasive because Chang evidences that it was known how to make a more lightly doped region under the heavily doped region within the substrate, and Slotboom '326 further evidences that it was also known how to make such lightly-over-heavily doped regions as taught by Ovshinsky, specifically in a bulk substrate (see e.g., FIG 2a, p+ region 3 and p region 4, and col. 4, lines 50-55).

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